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## ETCHING IN CHLORINE DISCHARGES USING AN INTEGRATED FEATURE EVOLUTION-PLASMA MODEL



Etching in Chlorine Discharges  
Using an Integrated Feature  
Evolution-Plasma Model

NASA Technical Reports Server  
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BiblioGov. Paperback. Book Condition: New. This item is printed on demand. Paperback. 32 pages. Dimensions: 9.7in. x 7.4in. x 0.1in. Etching of semiconductor materials is reliant on plasma properties. Quantities such as ion and neutral fluxes, both in magnitude and in direction, are often determined by reactor geometry (height, radius, position of the coils, etc. ) In order to obtain accurate etching profiles, one must also model the plasma as a whole to obtain local fluxes and distributions. We have developed...

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